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Substitute for form 1449A/PTO Complete if Known **Application Number** TO BE ASSIGNED (Div1) INFORMATION DISCLOSURE Filing Date March 8, STATEMENT BY APPLICANT First Named Inventor Bruce W. Smith Group Art Unit 2851 (use as many sheets as necessary) **Examiner Name** Hung NGUYEN

Attorney Docket Number

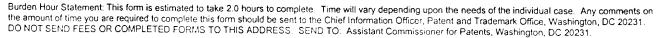
U.S. PATENT DOCUMENTS						
xaminer nitials	Cite No. ¹	U.S. Patent Document Number Kind Code (if known		Name of Patentee or Applicant of Cited Document	Date of Publication of Cited Document MM-DD-YYYY	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
M	1	5,627,625		Tohru Ogawa	05/06/97	
	2	5,638,211		Naomasa Shiraishi	06/10/97	
	3	3,776,633		Albert Frosch, et al	12/04/73	
\perp	4	3,729,252		Clarence N. Nelson	04/24/73	
\bot	5	5,926,257		Satoru Mizouchi	07/20/99	
$oldsymbol{ol}}}}}}}}}}}}}}}}}$	6	5,631,721		Stuart Stanton, et al.	03/20/97	
Li	7	5,673,102		Akiyoshi Suzuki, et al.	09/30/97	
#N	8	5,305,054		Akiyoshi Suzuki, et al.	04/19/94	
					·	

-	Cite No.1	Foreign Patent Document				Date of Publication of	Pages, Columns, Lines,	T-	
Examiner Initials		Office ³ Number ⁴		Kind Code ^s (if known)	Name of Patentee or Applicant of Cited Document	Cited Document MM-DD-YYYY	Where Relevant Passages or Relevant Figures Appear	Τ¢	
44	V_	9	EP	0 503 472 A3	EP	Minori Noguchi	09/16/92		T
\perp		10	EP	0 500 393 B1	EP	Akiyoshi Suzuki, et al.	08/26/92		
1		11	EP	0 500 393 A3	EP	Akiyoshi Suzuki, et al.	08/26/92		\top
1		12	EP	0 486 316 A3	EP	Naomasa Shiraishi	05/20/92		1
\perp		13	EP	0 496 891 A1	EP	Naomasa Shiraishi	08/05/92		1
Н	W	14	EP	0 783 135 A1	EP	Akiyoshi Suzuki, et al.	07/09/97		1
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/ Examiner	1	Date	1/10/2	
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Attorney Docket Number

		OTHER PRIOR ART NON PATENT LITERATURE DOCUMENTS				
Examiner Initials	No.1 No.1 No.1 No.1 No.1 No.1 No.1 No.1					
HN	15	S. Asai, et al., "High Performance Optical Lithography Using a Separated Light Source", J. Vac. Sci. Technology, Vol B 10(6), pp. 3023-3026, (November/December 1992).				
	16	E. Tamechika, et al.,"Investigation of Single Sideband Optical Lithography Using Oblique Incidence Illumination", J. Vac. Sci. Technology, Vol. B 10(6), pp. 3027-3031, (November/December 1992).				
	17	W.N. Partlow, et al., "Depth of Focus and Resolution Enhancement for i-line and Deep-UV Lithography Using Annular Illumination", SPIE Optical/Laser Microlithography, Vol. 1927, pp. 137-156, (1993).	-			
	18	T. Ogawa, et al., "The Effective Light Source Optimization With the Modified Beam For the Depth-of-Focus Enhancements", SPIE Optical Laser Microlithography, Vol. 2197, pp. 19-30, (1994).				
	19	T. Ogawa, et al., "Sub-Quarter Micron Optical Lithogrpahy With Practical Super Resolution Technique", SPIE Optical Laser Microlithography VIII, Vol. 2440, pp. 772-783, (1995).				
	20	B. W. Smith, et al., "Illumination Pupil Filtering Using Modified Quadrupole Apertures", SPIE Optical Microlighography XI, Vol. 3334, pp. 37-47, (1998).				
	21	B.W. Smith, et al., "Influences of Off-Axis Illumination on Optical Lens Aberration", J. Vac. Sci. Technology, Vol. B16(6) 3398, pp. 3405-3410, (November/December 1998).				
	22	Chin C. Hsia, et al., "Customized Off-Axis Illumination Aperture Filtering for Sub 0.18 um KrF Lithography", SPIE Optical Microlithography XI, Vol. 3679, pp. 39-46, (1999).				
	23	P. Zandbergen, et al., "Optical Extension at the 193nm Wavelength", SPIE Optical Microlithography XI, Vol. 3679, pp. 29-38, (1999).				
	24	Z. Yang, et al., "Corrections of Aberrations Using HOE's in UV and Visible Imaging Systems", <u>SPIE International Lens Deisgn Conference</u> , Vol. 1354, pp. 323-327, (1990).				
T HW	25	B. W. Smith, Microlithography: Science and Technology, Chapter 3, New York: Marcel Dekker (1998), pp. 216-231.				

Examiner H. Wgruyen	Date Considered	6/19/03	
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